

EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Further to the amendment dated 8/6/2009, Claim 1 is amended further as below:

A vapor phase growth apparatus comprising at least a sealable reactor, a wafer containing member installed within the reactor and having a plurality of wafer mounting portions along the same circumference on a front surface thereof for holding a plurality of wafers, a gas supply member for supplying raw material gas towards the wafers, a heating member for heating the wafers, and a heat uniformizing member for holding the wafer containing member and uniformizing heat from the heating member, the heating uniformizing member having approximately the same size as the wafer containing member, and

wherein raw material gas is supplied into the reactor in a high temperature environment while heating the wafer by using the heating member via the heat uniformizing member and the wafer containing member, to form a film grown on a surface of the wafer,

wherein a recess portion depressed in a dome shape is formed at a back surface of the wafer containing member to form a gap between the wafer containing member and the heat uniformizing member, and the recess portion is formed so that (i) an apex of the dome shape is arranged on a straight line connecting a center of the wafer containing member with a center of the heating uniformizing member and (ii) a maximum height of the gap is at the apex of the dome shape,

wherein the wafer containing member comprises a material having a heat conductivity of 50W/mK or larger but not exceeding 500W/mK, and

wherein, when a height and a diameter of the recess portion provided in the wafer containing member are represented by H and D, respectively, the height H is within a range from 0.02mm to 3.5mm and a ratio of the height and the diameter H/D is between 0.01 and 2.10%

Authorization for this examiner's amendment was given in a telephone interview with Ms. Venessa Perez on 9/18/2009.

2. Claims 1 and 3-7 are allowed.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ram N. Kackar whose telephone number is 571 272 1436. The examiner can normally be reached on M-F 8:00 A.M to 5:P.M.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on 571 272 1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Ram N Kackar/
Primary Examiner, Art Unit 1792